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(54) Title: PLASMA REACTOR WITH OVERHEAD RF ELECTRODE TUNED TO THE PLASMA

(57) Abstract: In accordance with one aspect of the invention, a plasma reactor has a capacitive electrode driven by an RF power source, and the electrode capacitance is matched at the desired plasma density and RF source frequency to the negative capacitance of the plasma, to provide an electrode plasma resonance supportive of a broad process window within which the plasma may be sustained.